

Session Title:	[WC1] Atomic Layer Etching
Session Date:	November 16 (Wed.), 2022
Session Time:	10:45-11:55
Session Room:	Room C (Grand Ballroom 2, 2F)
Session Chair:	Prof. Geun Young Yeom (Sungkyunkwan Univ., Korea)

[WC1-1] [Invited] 10:45-11:15

Conductor Etch Process - A Technical Review

Yeonghun Han (SK hynix, Korea), Sangjun Park (Applied Materials Inc., USA), and Sung Jin Jung (Lam Research, USA)

[WC1-2] 11:15-11:35

Atomic Layer Etching of Titanium Nitride with Plasma Oxidation and Fluorination

Heeju Ha and Heeyeop Chae (Sungkyunkwan Univ., Korea)

[WC1-3] 11:35-11:55

Isotropic Atomic Layer Etching Process for Al₂O₃ Film

Jun Hyuck Kwon, Ju Hwan Park, Sang Joon Park, Jin Sung Chun (Wonik IPS Co., Ltd., Korea), Yewon Kim, Khabib Khumaini, Gyejun Cho (Sejong Univ., Korea), and Won-Jun Lee (Sejong Univ., Korea)